

WHAT IS CLAIMED IS:

1. A method for creating a pattern on a substrate, the method comprising the step of:
 - (a) imprinting a first pattern on the substrate; and
 - (b) imprinting a second substantially similar pattern that is mis-registered with regard to the first pattern so that the combination of the first and second patterns causes a systematic variation in a final size of defined elements across the substrate.
2. The method as in claim 1, wherein step (b) includes providing the elements as structures used for an image sensor.
3. The method as in claim 2, wherein step (b) includes providing the element as an aperture.
4. The method as in claim 1, wherein step (b) includes providing the element as a micro-lens.
5. The method as in claim 1, wherein step (b) includes providing a mask as the substrate, which mask is used as a template for device fabrication.
6. The method as in claim 1, wherein step (b) includes providing a material upon which the device is fabricated as the substrate.
7. The method as in claim 3, wherein step (b) includes systematically increasing aperture size as the aperture approaches a periphery of the substrate.